## Photon Beamlines



## Photon Beamline

A photon beamline is everything necessary to transport the FEL photon beam, generated into the undulators, to the experimental chamber

## OUTLINE:

- Principle of X-ray optics
- Wavefront preserving optics: needs, production and measurement
- Optics damage handling
- Diffractive elements (wavelength diagnostic)
- Focusing elements



## Photon energy regions



SXR: These regions are very interesting because are characterized by the presence of the absorption edges of most low and intermediate $Z$ elements; photons with these energies are a very sensitive tool for elemental and chemical identification. PROBLEM: Absorption edges are bad things for photon transport
HXR: This region provide highly penetrating radiations, it is useful to study bulk rather than surface. The short wavelength make possible high spatial resolution microscopy or diffraction techniques. PROBLEM: penetration is not good for reflective optics.

## Refraction index

refractive index $\quad \mu=1-\delta-i \beta$


## Snell law



$\mathrm{n}>1$
$\mathrm{n}<1$


Snell's law: $\mathrm{n}_{1} \cos \gamma=\mathrm{n}_{2} \cos i$


Fermat's principle
The Light travels the path from A to B in the minimum possible time (valid for every wavelength)
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## Snell law - Lenses



$$
\delta \approx 10^{-4} \quad H X R \Rightarrow f \approx 1 m \quad \text { if } \quad R \approx 1 \mathrm{~mm}
$$

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## X-ray lens



## if $\quad R \approx 1 \mathrm{~mm}$

This could be, in principle, all you need

## Total external reflection



Snell's law: $\mathrm{n}_{1} \cos \gamma=\mathrm{n}_{2} \cos i$
Snell's law ( $\mathrm{n}_{1}=1$, vacuum):

$$
\cos \gamma=\cos i / n
$$

$$
\gamma=0 \mathrm{n}=\cos i_{\mathrm{c}}
$$

$\mathrm{i}_{\mathrm{c}}$ critical angle: total external reflection

$$
\begin{gathered}
\sin i_{\mathrm{c}}=\lambda\left(\mathrm{e}^{2} \mathrm{~N} / \pi \mathrm{mc}^{2}\right)^{1 / 2} \\
\lambda_{\mathrm{c}}(\mathrm{~min})=3.333 \cdot 10^{-13} \mathrm{~N}^{-1 / 2} \sin i_{\mathrm{c}}
\end{gathered}
$$

| Material | Density <br> $\left(\mathrm{g} / \mathrm{cm}^{3}\right)$ | N <br> $\left(\right.$ electron $\left./ \mathrm{cm}^{3}\right)$ | $\lambda_{\min }$ <br> nm |
| :--- | :---: | :---: | :---: |
| Pentadecane (oil) | 0.77 | $7 \times 10^{22}$ | $64.1 \sin i$ |
| Glass | 2.6 | $78 \times 10^{22}$ | $37.9 \sin i$ |
| Aluminum oxide | 3.9 | $115 \times 10^{22}$ | $31.2 \sin i$ |
| Gold | 19.3 | $466 \times 10^{22}$ | $15.4 \sin i$ |

$i=5^{\circ}: \quad \lambda_{\text {min }}$ glass $=3.3 \mathrm{~nm}=375 \mathrm{eV}$ $\lambda_{\text {min }}$ gold $=1.34 \mathrm{~nm}=923 \mathrm{eV}$

$$
\begin{aligned}
& \text { gold } \\
& 600 \mathrm{eV} \Rightarrow i_{\mathrm{c}} \approx 7.4^{\circ} \\
& 1200 \mathrm{eV} \Rightarrow i_{\mathrm{c}} \approx 3.7^{\circ} \\
& 5 \mathrm{keV} \Rightarrow i_{\mathrm{c}} \approx 0.9^{\circ}
\end{aligned}
$$

## Mirror reflectivity and critical energy Soft X-ray

SLAC




## Mirror Reflectivity and critical angle (Hard X-ray)




## Mirror dimension



$1 \mathrm{~mm} / \sin \left(0.2^{\circ}\right)>1.5 \mathrm{~m}$

$4-5 \mathrm{~mm} / \mathrm{sin}\left(2^{\circ}\right)<200 \mathrm{~mm}$
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## Defect effect

Object


Tangential focusing


## Defect effect



$$
\Delta s^{\prime}=2 r^{\prime} \sigma
$$

Object


## Defect effect (slide made on 2004)

$$
\Delta s^{\prime}=2 r^{\prime} \sigma
$$




## Capabilities (SR suppliers) (updated)

## Typical manufacturer capabilities (SESO, zEISS, Winlight, Insync)

| Shape | Length | rms errors |
| :--- | :--- | :--- |
| Spherical/flat | Up to 500 mm | $<0.1 \mu \mathrm{rad}$ |
| Spherical/flat | $>500 \mathrm{~mm}$ | $<0.5 \mu \mathrm{rad}$ |
| Toroidal | Up to 500 mm | $\sim 1 \mu \mathrm{rad}$ |
| Toroidal | $>500 \mathrm{~mm}$ | $\sim 2 \mu \mathrm{rad}$ |
| Elliptical | Up to 500 mm | $\geq 1-2 \mu \mathrm{rad}$ |
| Elliptical | $>500 \mathrm{~mm}$ | $>2 \mu \mathrm{rad}$ |



## Capabilities

State of the art SR manufacturer capabilities



## FEL mirrors (shape errors)

Strehl Ratio $\approx \mathrm{e}^{-(2 \pi \varphi)^{2}} \approx 1-(2 \pi \varphi)^{2}$
$\varphi=\frac{2 \delta h \sin \vartheta}{\lambda}$ $\varphi$ is the wave distortion (phase)

The Strehl Ratio (SR) is defined as a ratio of the maximum intensity in the focus, with and without wave front distortions which are introduced by the optics


## Shape errors effects

The Marechal Criterion states that a good optical system has a $S R \geq 0.8$; e.g. In focus: the Gaussian spot intensity is $\geq 0.8$ of the unperturbed Gaussian spot intensity

Simulations of 3 mirrors in one direction and 1 in the other for a global SR of 0.8


## Shape errors effects

We need better...........


## How to compensate wavefront distortions

SILAC


HXR; $1.35 \mathrm{mrad}, 13 \mathrm{keV} \rightarrow \mathbf{0 . 5 6} \mathbf{n m} \mathbf{~ r m s}$ SXR; $12.0 \mathrm{mrad}, 1.3 \mathrm{keV} \boldsymbol{\rightarrow} \mathbf{0 . 6} \mathbf{n m} \mathbf{~ r m s}$


| Angle of <br> incidence <br> (mrad/deg) | Photon <br> Energy <br> $($ KeV $)$ | Shape <br> error (nm) |
| :--- | :--- | :--- |
| $1.35 / 0.077$ | 5 | 4.6 |
|  | 20 | 1.1 |
|  | 13 | 1.78 |

## Mirror shape errors FEL



## Wavefront Preservation - acceptance

Affected by truncation (limited acceptance) and wavefront deformation (shape errors)


2 FWHM accept.


1 FWHM accept.


The LCLS mirrors were procured according to the state of the art availability e.g.
450 mm long mirrors with 2 nm rms shape error (compromise between shape and length)

Out of focus beam


LCLS is upgrading the mirrors with better figure and larger acceptance

## State of the art evolution


*LCLS mirrors are specified in height (nm rms).

## Polishing (CCP) effect

SLAC


Estimated best quality: 2-3 nm rms; $0.5 \mu \mathrm{rad} \mathrm{rms}$

## Ion beam finishing



## Ion beam finishing



Estimated best quality: $1 \mathrm{~nm} \mathrm{rms} ; 0.1 \mu \mathrm{rad} \mathrm{rms}$
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## Preferential deposition technique




1) Classical polishing
2) High precision metrology
3) Error correction by Rh controlled deposition
4) Second itaration with metrology
5) Second differential coating deposition
6) Third.....
7) ......
8) 
9) 

nn) Final required slope/shape error reched (hopefully)

Estimated best quality:
2-3 nm rms; $0.1 \mu \mathrm{rad} \mathrm{rms}$

## Elastic Emission Machining - Jtec

Processing technique to flat a surface in an atomic level


## Strong Points :

1. Owing to processing at an atom level, it is possible to be flatted at an atom level.
2. For chemical processing, no distortion on surface. 3. For regional processing by numerical control, it is possible to make various shape of mirrors.

Pre-polishing (1.3 nm rms)


> Measuring


Apply atomic level correction ( 0.14 nm rms )

## Elastic Emission Machining - Jtec - Performance

Processing technique to flat a surface in an atomic level


Roughness : $0.056 \mathrm{~nm}(0.6 \AA$ ) rms


Measured best quality: 0.2 nm rms; $0.05 \mu \mathrm{rad} \mathrm{rms}$

## State of the art evolution



Metrology improvement drove the mirror manufacturing improvement and, ultimately, push the science forefront limits*
*....ok... it's a bit of a stretch...

## Power Spectral Density

The rms deviation from the ideal surface at different periods is called the Power Spectral Density


$$
\sigma=\left(\int_{f_{\min }}^{f_{\max }} P S D(f) d f\right)^{1 / 2}
$$

## A metrology lab

Clean Room class 10,000 minimum, 1,000 ideally. Thermo stabilized within $\pm 1^{\circ}$ minimum ( $0.1^{\circ}$ or better ideal)


## LTP / NOM

Direct slope measurement 50 nrad slope error accuracy ( 0.1 nm rms accuracy) after proper calibration and environmental control Single trace measurement up to $1.2-1.5 \mathrm{~m}$ in length. Minimum spatial period covered ~ 1 mm


Interferometer
Direct height measurement
~ 0.5 nm rms after proper calibration and environmental control.
2D images up to 6' diameter Possibility of stitching reducing the accuracy. Minimum spatial period covered $\sim 0.05 \mathrm{~mm}$


White light micro interferometer
Direct heigth measurement
0.1 nm rms in proper environmental condition.
2D images up to $\sim 0.5 \mathrm{~mm}^{2}$
Minimum spatial period covered ~ $0.5 \mu \mathrm{~m}$

## Long Trace Profilometer

We need something to measure accurately ( 0.1 nm rms ) mirror with length up to 1 m minimum ( 1.5 m future prevision) and with arbitrary surface profile


LTP
P. Takacs, S.N. Qian, S. Irick

## By using an autocollimator

THE autocollimator to use is the Elcomat 3000/10 (by Möller-Wedel)

- Works in presence of multiple reflections
- Specifically developed for metrology application
- Simple repeatability 100 nrad (10 nrad averaging)
- Un-calibrated accuracy: 200 nrad over $100 \mu \mathrm{rad}$ (fix distance).
- Accuracy worst than $1 \mu$ rad in the entire field of view.
- 10 mrad field of view


Precise but needs a lot of calibration

## Fizeau Interferometer



3(D measurement of optical surfaces Zygo specs: $\lambda / 500$ precision Tipical: $\lambda / 2-3000$ repeatability

Direct measurement of radii down to $20-30 \mathrm{~m}$
Optional Accessories
Transmission spheres
$\mathrm{f} / 1.5-2$ for sagittal radii and NI mirrors with $\mathrm{R}<1 \mathrm{~m}$
$\mathrm{f} / 15-30$ diverger for NI mirrors with $\mathrm{R}>2 \mathrm{~m}$

## Optical surface damage

Above the grazing critical angle


The non reflected energy is absorbed (1/e) in $d>$

$$
\begin{array}{r}
d=\frac{\lambda \zeta}{4 \pi \beta} \\
\zeta=\sqrt{\frac{\sin ^{2} \theta-2 \delta+\sqrt{\left(\sin ^{2} \theta-2 \delta\right)^{2}+4 \beta^{2}}}{2}}
\end{array}
$$

$$
n=1-\delta-i \beta
$$

$$
\delta=\frac{N e^{2} \lambda^{2}}{2 \pi m c^{2}}
$$

Below the grazing critical angle

$\mathrm{R}=$ reflectivity
$P=$ pulse power
$\theta=$ angle of incidence
$r=$ source distance
$\sigma=$ source divergence
$\rho=$ atomic density

$$
\text { Aborbed } \text { Energy }_{\text {ATOM }}=\frac{(1-R) P \sin \vartheta}{r \sigma_{x} \sigma_{y} d \rho}
$$

Ideal coating should have a large penetration depth (light materials) and good reflectivity (usually associated with heavy materials)

## Optical surface damage

LCLS II case: 200 to 1300 eV with 2 mJ incident pulse energy

Try to work at the lowest possible angle of incidence spread the power over a large surface


## Energy absorbed vs critical angle




## Example of damage for UV sources (Fermi@Elettra)



Measured at 400 nm at the EIS laser lab

## Test on LCLS mirror samples



## Dispersive elements



| Micro <br> wave | I.R. | Visible | U.V. | Soft <br> X-ray | Hard <br> X-ray |
| :--- | :---: | :---: | :---: | :--- | :--- |



$$
\text { limit ~ 1-2 keV ( } 1 \mathrm{~nm} \text { ) }
$$

| Micro <br> wave | I.R. | Visible | U.V. | Soft <br> X-ray | Hard <br> X-ray |
| :--- | :---: | :---: | :---: | :--- | :--- |


$n \lambda=d(\sin (\alpha)-\sin (\beta))$

## Grating profiles

SLAC


Higher efficiency


Higher spectral purity Higher resolving power


## Grating Efficiency



Efficiency as a function of the groove depth for two different photon energies

## Grating Damage (laminar)



A lot of energy deposited on the grating facet


## Grating Damage (blaze)



A lot of energy deposited on the grating facet


Energy distributed on the grating facet

## Damage tests on gratings



Fig. 1. (Color online) Top: schematic of the interaction of the experiment. Below: DIC microscopy (left) and AFM (right) measurements for three different fluences 356 (A), 806 (B), and $1115 \mathrm{~m} . / \mathrm{cm}^{2}$ (C).

The reported damage threshold ( $0.5 \mathrm{eV} / \mathrm{atm}$ ) is 3 times lower the observed on a flat mirror. $1.5 \mathrm{eV} /$ atom $)$
Optics Letter Vol. 37 (15) 2012, 3033


Single Shot damage ~ 8-10 eV/atom
Multi shot damage $\sim 720 \mathrm{meV} /$ atom
Defined the maximum working energy for the Pt grating according to these tests

## Damage tests on gratings



Result still under investigation but, it looks like that the grating has the same damage threshold of a mirror with an angle of incidence identical to the angle of the grating facet with respect the radiation. It means, the blaze angle shall be really small!

## Mechanically ruled grating

- Thermal evaporation of Gold



## Si substrate

## Mechanically ruled grating - toward very shallow blaze angle

- Thermal evaporation of Gold on the Si substrate (plus Cr binding layer)
- Grooves formed by plastic deformation of the ruling layer
 -Realization of low microroughness blaze grating with $20<\mathrm{gd}<5000 \mathrm{l} / \mathrm{mm}$ and down
- to $1.5^{\circ}$ of blaze angle
- Ar ${ }^{+}$ion etching ( 200 mm diameter collimated beam)
- $\mathrm{Ar}^{+}$ion etching rate on gold much larger then on Silicon
- An angle reduction of a factor 3 (even higher if $\mathrm{Ar}^{+}+\mathrm{O}^{+}$is used) can be achieved by this technique
- Roughness and anti blaze angle are also reduced.


## Shallow Blaze Angle grating



> Plane substrate $600 \mathrm{l} / \mathrm{mm}$ gold coated $80 \times 5 \mathrm{~mm}$ useful area, 6laze angle $0.4^{\circ}$


## On Line Spectrometer

Groove density expanded in Taylor series

$$
D(y)=D_{0}+D_{1} y+D_{2} y^{2}+\ldots
$$

Beam from source
$1^{\text {st }} / 2^{\text {nd }}$ internal order to detector (~0.1-3\%)

Zeroth order $\frac{\text { to the beamlines }}{(\sim 97 \%)}$
$D<; \beta>$
D> : $\beta$

Movable Detector YAG+CCD

$$
r^{\prime}(E), \beta(E)
$$



## Measured HGHG Seeded FEL beam



Curtesy of Fermi@Elettra - PADReS

## FEL Monochromator

To survive and handle the variable focal
Flat mirror distance (without adaptive optics involved) the
Fixed incidence
angle VLS grating grating must be a VLS of more than 500 mm in length

Variable source distance

Fixed focal distance and direction


Source position calculated by J. Krzywinski

## Pulse Length preservation



$$
\Delta t=\sqrt{\left(\frac{N \lambda}{c}\right)^{2}+\delta t^{2}}
$$

## Pulse Length preservation

Need of long substrates to distribute the power:
$1200 \mathrm{l} / \mathrm{mm}$ grating, $500 \mathrm{~mm}, 500 \mathrm{eV}$
$\sim 5,000$ fsec
$10 \mathrm{l} / \mathrm{mm}$ grating, $500 \mathrm{~mm}, 500 \mathrm{eV}$
$\sim 40$ fsec
1-100 fs


$$
\Delta t=\sqrt{\left(\frac{N \lambda}{c}\right)^{2}+\delta t^{2}}
$$

## Conical Diffraction


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## Bragg Law



EXAMPLES: $\quad \operatorname{Si}(111) d=3.13 \AA \rightarrow$ Emin $\approx 2 \mathrm{KeV}$

$$
\operatorname{InS6}(111) d=3.74 \mathscr{A} \rightarrow \text { Emin } \approx 1.7 \mathrm{KeV}
$$

Radiation of wavelength $\lambda$ is reflected by the lattice plane. The outgoing waves interfere. The interference is constructive only if the difference of optical path is a multiple of $\lambda$ :

## $2 d \sin \vartheta=n \lambda$

Limits:

## $\sin \vartheta=1 \Rightarrow \lambda_{\max }$

$$
\lambda_{\max }=2 \mathrm{~d} @ \theta=90^{\circ}
$$

$$
\operatorname{Si}(311) d=1.64 \AA \rightarrow \text { Emin } \approx 3.8 \mathrm{KeV}
$$

$$
\operatorname{Beryl}(1010) d=7.98 \AA \mathscr{A} \rightarrow \text { Emin } \approx 0.8 \mathrm{KeV}
$$

## Spectrographs

Grating based spectrometer (Soft X-ray)

## Measurement of the LCLS HXR SASE spectrum



## 2D focusing - 1 mirror option - Ellipsoid



## 2D focusing - 1 mirror option - Ellipsoid



## 2D focusing - 2 mirrors option

## Formation of Optical Images by X-Rays

Paul Ktheateick and A. V. Bapz Stanfard Unibersily, Slamfard, California
(Received March 12, 1048)

Several conceivable methods for the formation of optigal images by $x$-rays are considered, and a method employing concave mirrors is adopted as the most promising. A concave spherical mirror receiving radiation at grazing incidence (a necessary arrangement with $x$-rayn) images a polnt isto a line in accordance with a focal length $f=R / / 2$ where $R$ is the radias of curvature and i the graxing angle. The imase is subtient in an ahereatinn surh that a rav
point of central rays by a distance given approximately by $5=1.5 \mathrm{M} r^{2} / R$, where $M$ is the magnification of the image and $r$ is the radius of the mirror face. The theoretlcally possible resolving power is such as to resolve point objects separated by about 70A, a limie which is independent of the wavelength used. Point inages of points and therefore extended images of extended objects may he nondareat twe mastion the madistion on mellers formen amo

This optical configuration is generally known as KB optics.
Could be made by 2 spherical mirrors, two elliptical mirror or other shapes, static or adaptive.


Vertical focusing mirror

Horizontal focusing mirror


## 4 cylinders bender (SESO)



## ESRF Trapezoidal Bender



Need to control at least 3 parameter to approximate an ellipse starting from a flat


## ESRF Trapezoidal Bender

SLAC


ID 22 Spot size measurement


Horizontal scan


## KB system for high power FELs

With high repetition FELs, for the very first time, the active optics shall, also, be cooled*

Radiation focused on two separate experimental position

Previous mirrors


Virtually no residual rms slope errors when focusing in the $1^{\text {st }}$ chamber

Residual rms slope errors when focusing in the second chamber

HFM: $0.13 \mu \mathrm{rad} \longrightarrow \sim 3 X 5 \mu \mathrm{~m}^{2}$ spot $2^{\text {nd }}$ chamber
VFM: $0.42 \mu \mathrm{rad} \longrightarrow$

## Wavefront distorsion compensation



## Bimorph Mirrors



## Correction Matrix



## Shape Correction



$$
\mathrm{R}=4.5 \mathrm{Km}
$$

## Zone Plate

SLAC


## Zone Plate

$$
\sin \theta_{m}=\frac{m \lambda}{d} ; \quad m=0, \pm 1, \pm 2, \pm 3
$$



## Zone Plate

$$
r_{n}^{2}=f n \lambda \quad l \begin{aligned}
& q_{n}+p_{n}=q+p+\frac{n \lambda}{2} \\
& q_{n}=\left(q^{2}+r_{n}^{2}\right)^{1 / 2} \simeq q+\frac{r_{n}^{2}}{2 q} \\
& p_{n}=\left(p^{2}+r_{n}^{2}\right)^{1 / 2} \simeq p+\frac{r_{n}^{2}}{2 p} \\
& q+\frac{r_{n}^{2}}{2 q}+\not p+\frac{r_{n}^{2}}{2 p} \simeq \not q+\not p+\frac{n \lambda}{2} \\
& \frac{1}{q}+\frac{1}{p} \simeq \frac{n \lambda}{r_{n}^{2}}
\end{aligned}
$$

## Zone Plate



## Zone Plate



## Zone Plates under FEL beam



## High Aspect Ration Zone Plate



Scanning electron microscope (SEM) images of zone plates pattern produced with the V-MACE technique.
(Ref. Chieh Chang, Anne Sakdinawat)

Very good efficiency on the HXR but... does it survive the FEL radiation?


## Literature

Books/tutorials

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